

| Ref # | Hits | Search Query                                                                                                      | DBs                      | Default Operator | Plurals | Time Stamp       |
|-------|------|-------------------------------------------------------------------------------------------------------------------|--------------------------|------------------|---------|------------------|
| L1    | 0    | plate and (phase adj shift) and (polygonal adj etch adj window) and (electromagnetic adj wave)                    | USPAT; EPO; JPO; DERWENT | OR               | OFF     | 2005/07/24 17:43 |
| L2    | 0    | plate and (phase adj shift) and (polygonal near5 etch\$3 near5 window) and (electromagnetic adj wave)             | USPAT; EPO; JPO; DERWENT | OR               | OFF     | 2005/07/24 17:44 |
| L3    | 12   | plate and (phase adj shift) and polygonal and (electromagnetic adj wave)                                          | USPAT; EPO; JPO; DERWENT | OR               | OFF     | 2005/07/24 17:51 |
| L4    | 0    | ((integrated adj circuit) or IC) and substrate and (phase adj shift) and polygonal and (electromagnetic adj wave) | USPAT; EPO; JPO; DERWENT | OR               | OFF     | 2005/07/24 17:51 |
| L5    | 10   | substrate and (phase adj shift) and polygonal and (electromagnetic adj wave)                                      | USPAT; EPO; JPO; DERWENT | OR               | OFF     | 2005/07/24 17:51 |
| L6    | 2    | 5 not 3                                                                                                           | USPAT; EPO; JPO; DERWENT | OR               | OFF     | 2005/07/24 17:52 |